

Electrohydrodynamic (EHD) Cleaning for C_{RES} Reduction in a High Volume Production Environment - An Engineering Evaluation

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Overview

- **Cantilevered Probe Cleaning Problems to Address**
- **Commonly Used Cleaning Techniques**
- **Fine Pitch Cleaning Issues**
- **EHD Cleaning for Contact Resistance Reduction**
- **Mechanisms Behind EHD**
- **Benefits for High Volume Production**
- **Engineering Evaluation**
- **Summary**

Cantilevered Probe Problems to Address

- **Probing is a “dirty business”**
 - ◆ Residues from wafer processing
 - ◆ Adherent particulates
 - ◆ Bond pad and probe needle surface oxides
 - ◆ Temperature effects, i.e. hot chuck testing, high current
 - ◆ High C_{RES} leads to yield fallout and reprobe
- **Maintenance of clean probe contact surface**
 - ◆ “Clean” probes provide low and stable C_{RES}
 - ◆ Quality of the intermetallic contact at conductive a-Spots
 - ◆ Short setup time and consistent prober/tester uptime

Commonly Used Cleaning Techniques

- **Burnishing on an abrasive surface**
 - ◆ 0.5, 1.0, 3.0, and 5.0- μm grit lapping film
 - ◆ 10- μinch finish tungsten-carbide cleaning plate
 - ◆ Ceramic cleaning chuck
 - ◆ Efficient for reducing C_{RES} at the cost of probe damage

- **“Non-destructive” techniques**
 - ◆ Manual brushing with or without IPA
 - ◆ Ultrasonic cleaning and DI-water rinse
 - ◆ Detergent and water immersion
 - ◆ CO_2 Snow
 - ◆ Variable effects on C_{RES} at the cost of P&A integrity

Fine Pitch Abrasive Cleaning Issues

- **Current abrasive cleaning processes reduce C_{RES}**
 - ◆ Reduced pad sizes ⇒ sensitivity to non-planarity and misalignment
 - ◆ Smaller probe diameters ⇒ damage from frictional shear stresses
 - ◆ Smaller probe tips ⇒ coarse deformation of probe contact surface
 - ◆ Increased power requirements ⇒ oxidation and burnt probes
 - ◆ Excessive abrasive cleaning ⇒ reduced probe card life (\$\$\$)
- **Also, current cleaning processes are not “new” probe card technology friendly**
- **Clearly, there is a need to investigate an option for maintaining low C_{RES} without reducing the service life of these fine pitch probe cards**

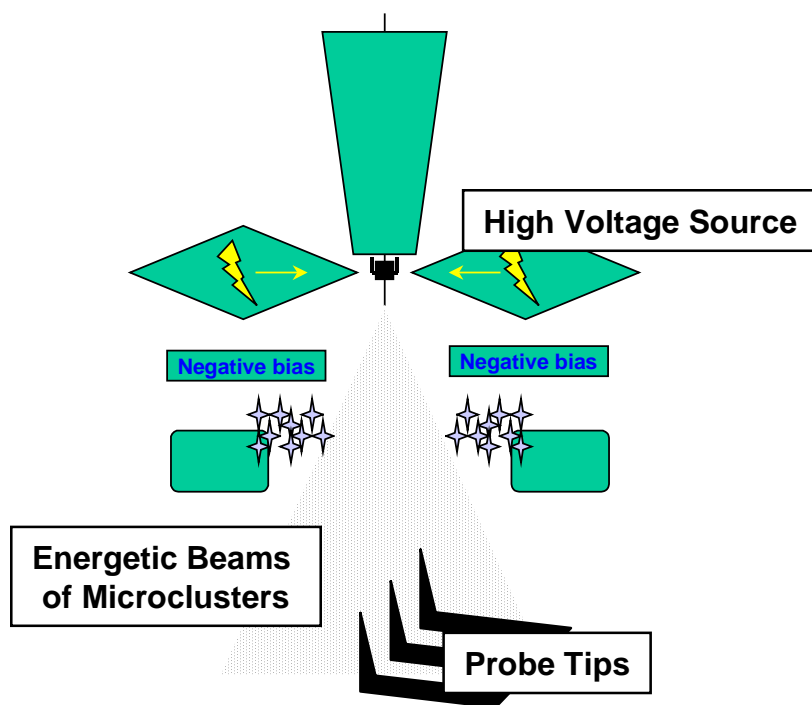
EHD Cleaning for C_{RES} Reduction

- How does it work?

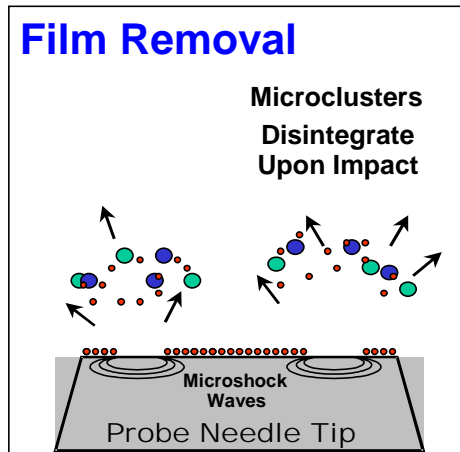
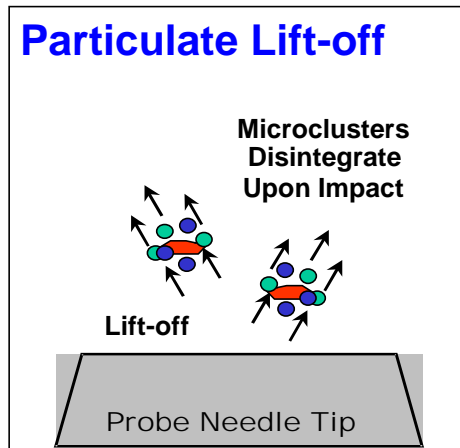
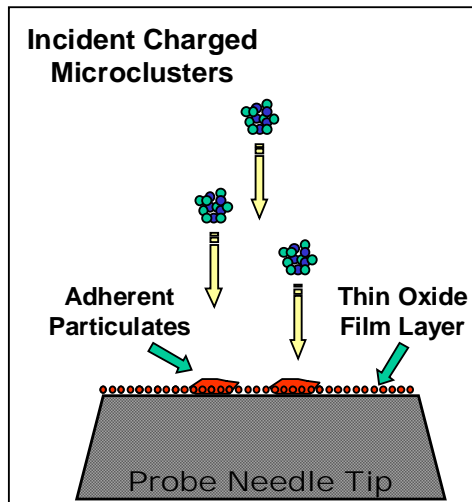
- ◆ Non-destructive
- ◆ Fab-safe cleaning media
- ◆ Requires a vacuum
- ◆ Relatively fast compared to other methods

- In a Production Environment

- ◆ Small footprint
- ◆ Programmable recipes
- ◆ Minimal operator training
- ◆ Off-line cleaning only
- ◆ Probe card PM schedule



Mechanisms Behind EHD



- **Particle lift-off**
 - ◆ “Massive” molecular clusters impact adherent particulates
 - ◆ Impulsive forces overcome van der Waal adhesion
 - ◆ Particulates are lifted off

- **Subsurface microshocks**
 - ◆ Molecular clusters travelling at hypervelocities
 - ◆ Microshock waves propagate along the probe surface
 - ◆ Material unloading due to passage of pressure waves

Benefits for High Volume Production

- **Effectively maintain low and stable probe C_{RES}**
 - ◆ Reduce “false fails” to increase yield
 - ◆ Minimize the need for reprobe
 - ◆ Decrease operator intervention
 - ◆ Extend probe card service life
- **Overall benefits to productivity and utilization**
 - ◆ Increased equipment up-time
 - ◆ Improved cycle-time and throughput
 - ◆ Improved cost of ownership (COO)

What we have been told.....

..... And what we really don't know.....

- **What have we been told about EHD cleaning?**
 - ◆ Reduces contact resistance
 - ◆ Removes aluminum and Al_2O_3 probe tips
 - ◆ Leaves no residuals on probes or bond pads
 - ◆ Non-destructive to probe contact surface

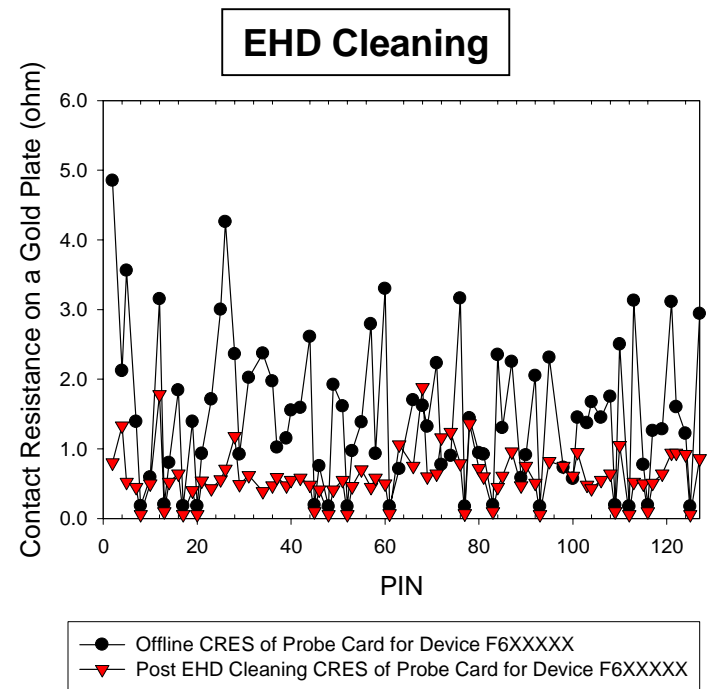
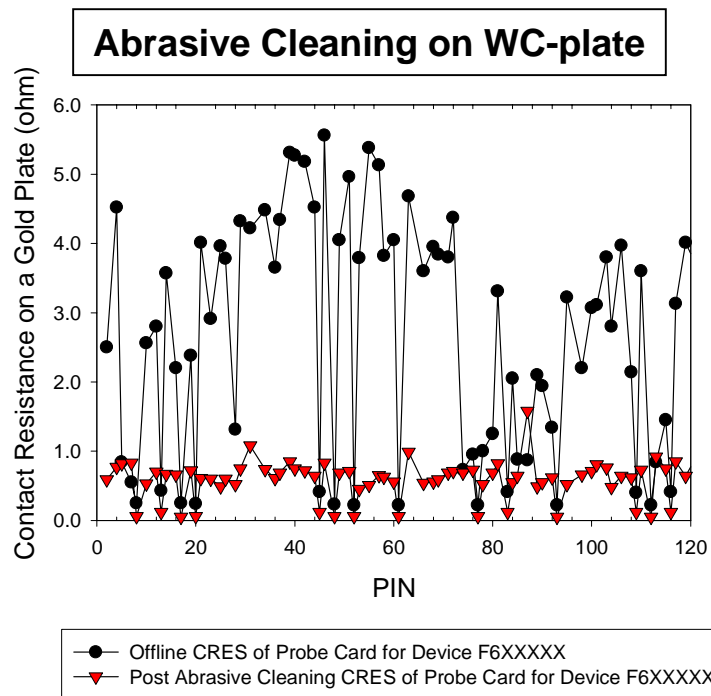
- **What do we need to learn?**
 - ◆ Damage to probe card materials
 - Epoxy ring
 - Ceramic guide plate
 - Printed circuit board
 - ◆ Long-term benefits on probe cards (if any)
 - ◆ Positive (or negative) effects on yield

Engineering Evaluation - Part 1

“Technology Validation”

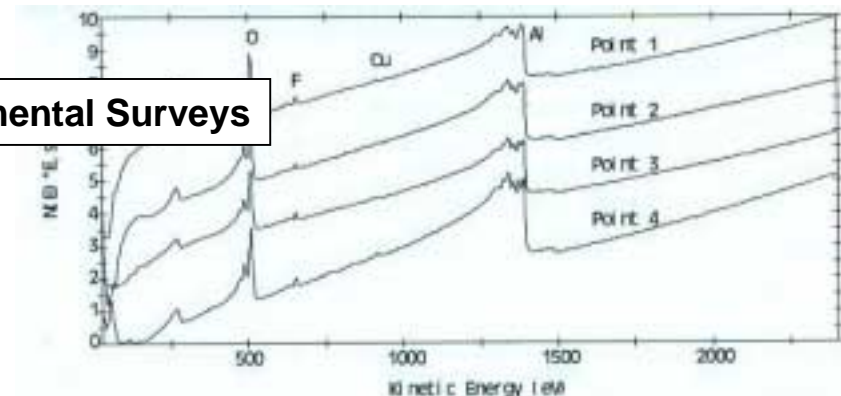
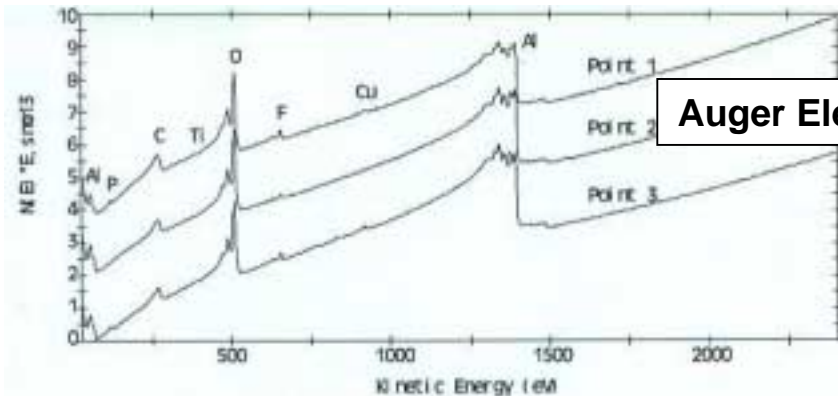
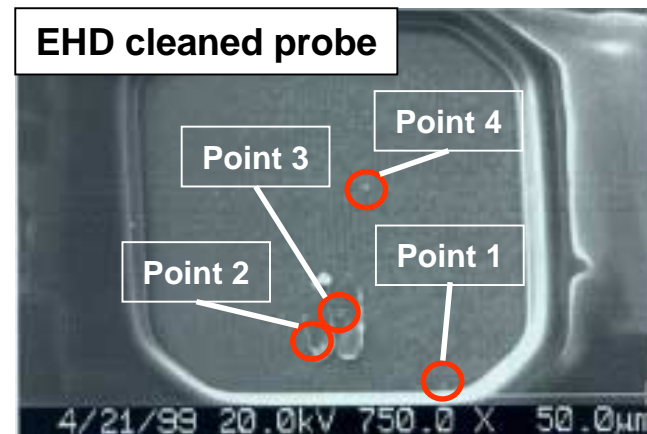
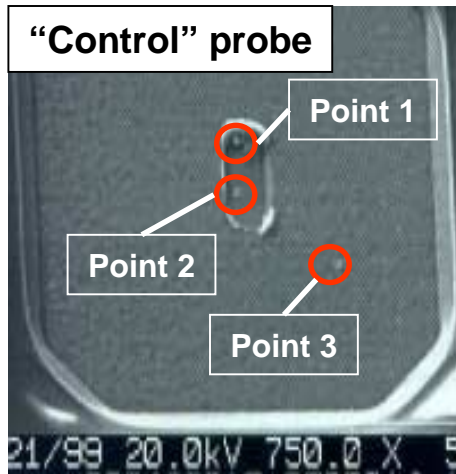
C_{RES} Reduction (EHD vs. Abrasive)?

- Representative Production Probe Cards
 - ◆ All cards had been regularly used to probe Al-bond pads
- For typical cards, EHD cleaning reduced the C_{RES} to a level comparable to that attained with off-line abrasive cleaning



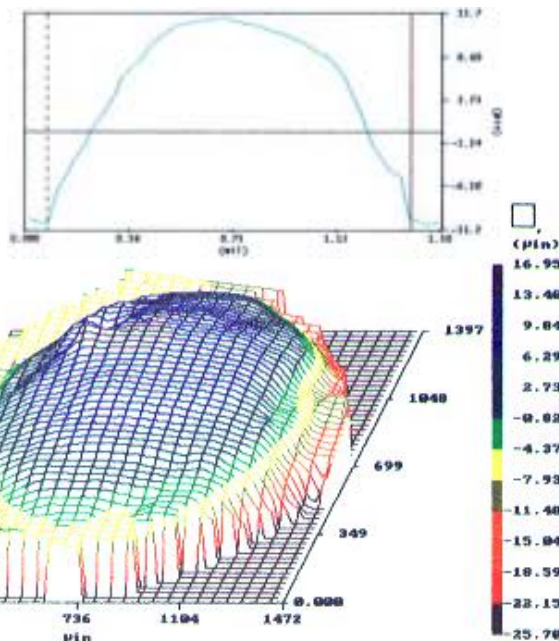
Residuals on Bond Pads?

- No residue from the EHD cleaned probes was observed on the bond pad or in the scrub marks



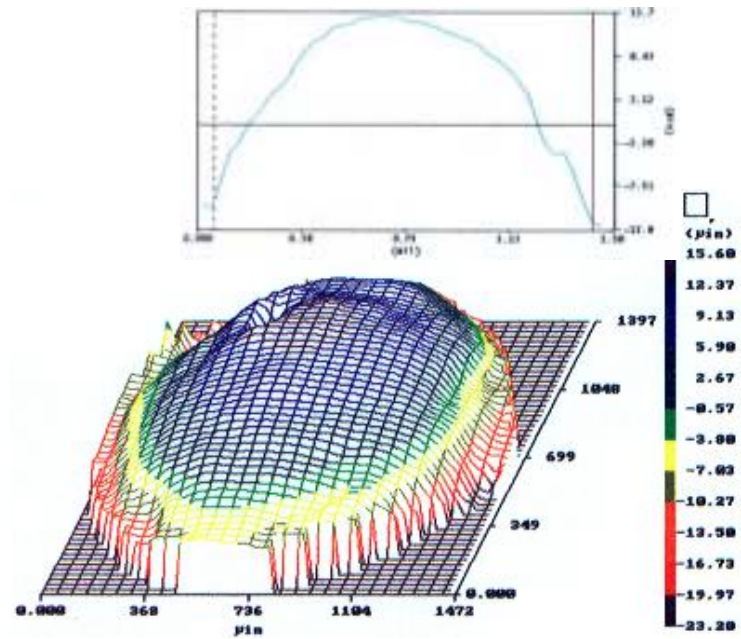
Non-destructive to probe contact surface?

Tip Surface 2D Profile



Probe as received from vendor

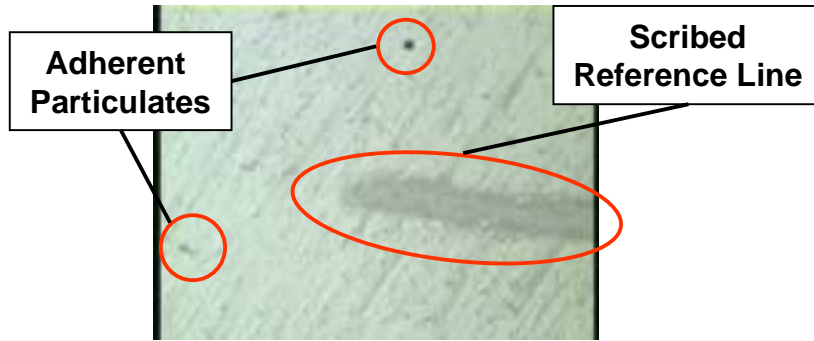
Tip Surface 2D Profile



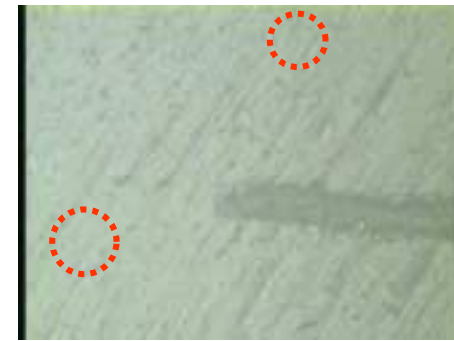
EHD Cleaned Probe Tip

- Probe surface topography was unchanged by EHD cleaning
- No discernable changes in probe planarity and alignment

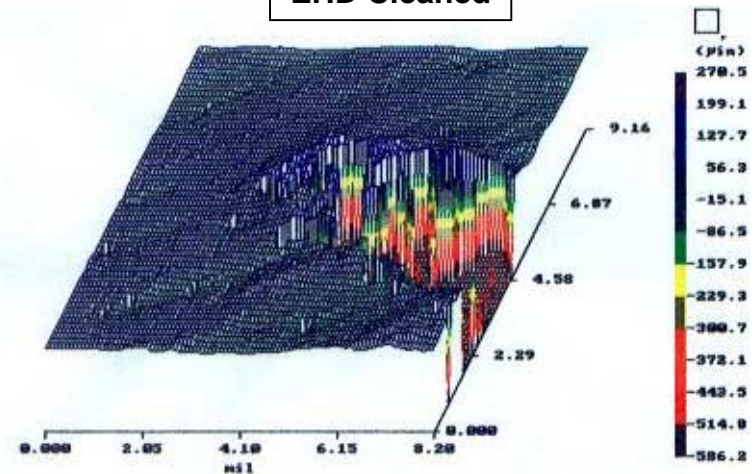
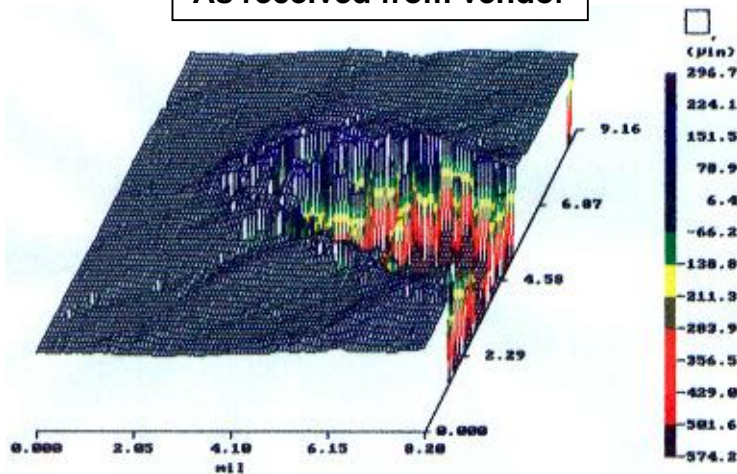
Damage to Card Materials - Epoxy?



As received from vendor

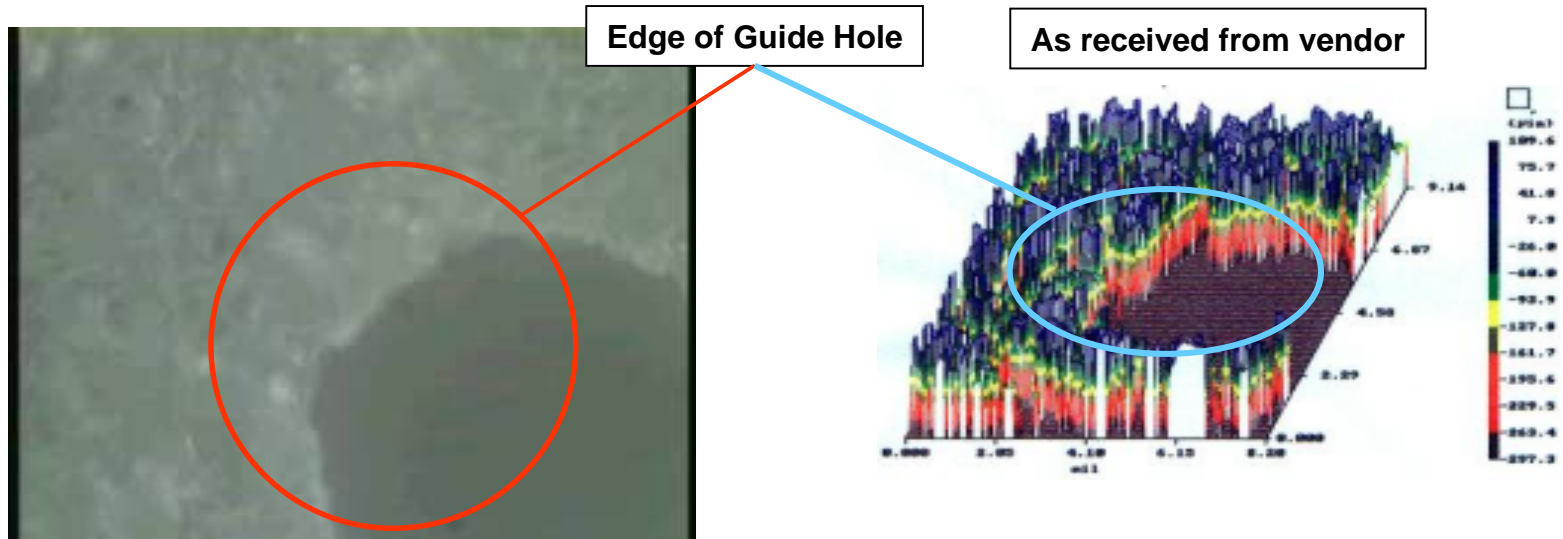


EHD Cleaned



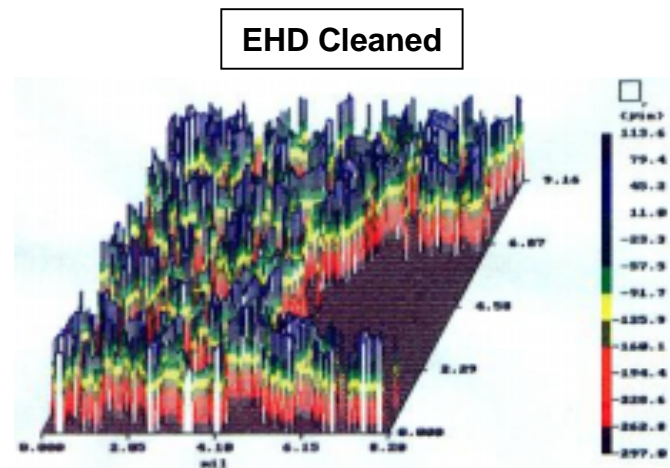
- Adherent particulates were removed from the surface
- Sharp corners of a scribed reference line were unaffected
- The contours of the surface were unchanged

Damage to Card Materials - Ceramic?



- **Ceramic lower die (guide plate)**

- ◆ Adherent contaminants associated with probing were removed from the surface
- ◆ Overall surface texture was not discernibly changed



Engineering Evaluation - Part 2

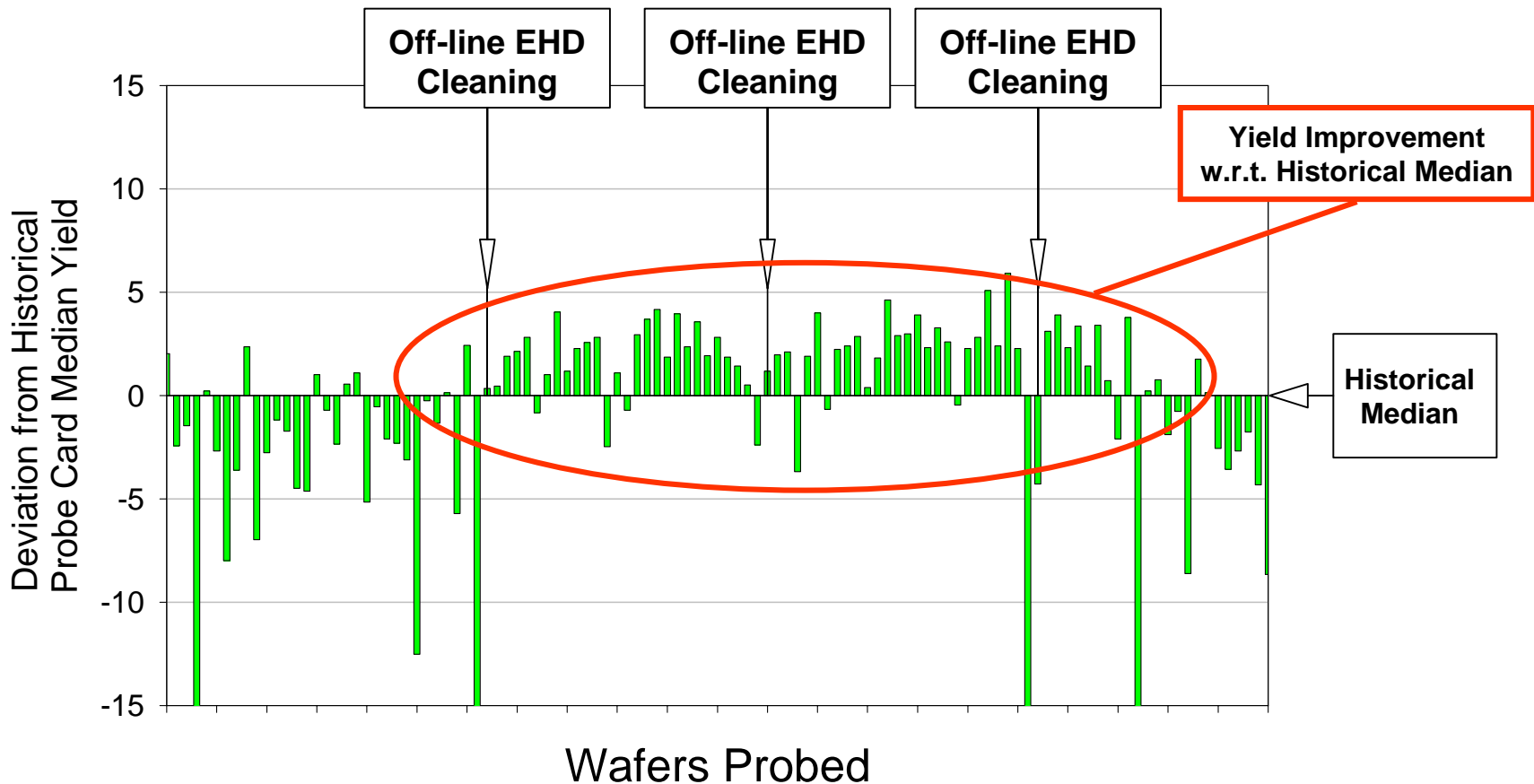
“We still have lot to learn...”

On the Probe Floor - Long Term Evaluation

- **High volume devices sensitive to C_{RES} stability and variation**
 - ◆ Fine pitch, dual-site cantilevered probe cards
 - ◆ Probe cards with production track records (historical)
- **Probe card metrology and cleaning procedures**
 - ◆ Baseline C_{RES} , leakage, BCF, and P&A
 - ◆ Off-line cleaning procedures
 - 10- μ inch, WC-abrasive plate
 - EHD cleaning
 - ◆ Re-evaluation of C_{RES} , leakage, BCF, and P&A
- **Monitoring of wafer yield and reprobe rates**
 - ◆ Within lot pre- and post cleaning yield assessments
 - Deviations from historical values assessed
 - ◆ Lots split across several probers (planned)
 - Parent lot (standard card); child lot (EHD cleaned card)

Preliminary Production Floor Results

- Observed yield fallout (i.e., poor probe card performance)
- Yield recovery exhibited after off-line EHD cleaning



EHD Evaluation Summary

- **Off-line Fine Pitch Probe Card Cleaning**
 - ◆ Effective for reducing C_{RES}
 - ◆ Viable alternative to abrasive cleaning
 - ◆ Non-destructive to probes, epoxy, and ceramic
 - ◆ No detectable residues observed within (or outside) of scrub marks
- **Long term evaluations in a production environment**
 - ◆ Yield fallout and reprobe
 - ◆ Equipment utilization
 - ◆ Probe card life
 - ◆ Ongoing and long-term benefits
- **Difficulties**
 - ◆ “Onions, onions, and more onions”